

UNITED STATES PATENT AND TRADEMARK OFFICE  
CERTIFICATE OF CORRECTION

PATENT NO. : 7,737,053 B2  
APPLICATION NO. : 10/579239  
DATED : June 15, 2010  
INVENTOR(S) : Koichiro Tanaka et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

At column 8, line 15, please change “ $\frac{s}{L} = \frac{M1}{M1}$ ” to --  $\frac{s}{L} = \frac{M1}{M2}$ --;

At column 8, line 17, please change “ $\frac{1}{f} = \frac{1}{M1} + \frac{1}{M1}$ ” to --  $\frac{1}{f} = \frac{1}{M1} + \frac{1}{M2}$ --;

At column 8, line 4, please change “/is the focal length” to --f is the focal length--;

At column 8, lines 7 and 8, please change “M1 is the distance between the first cylindrical lens 104 and the semiconductor substrate 106” to --M2 is the distance between the first cylindrical lens 104 and the semiconductor substrate 106--;

At column 9, lines 10-11, please change “ $D_F = K_T/PC_p$ , wherein  $K_T$  represents thermal conductivity,  $p$  represents density” to -- $D_F = K_T/\rho C_p$ , wherein  $K_T$  represents thermal conductivity,  $\rho$  represents density--;

At column 9, line 13, please change “density  $p$  of” to --density  $\rho$  of--;

At column 9, line 39, please change “suicide” to --silicide--;

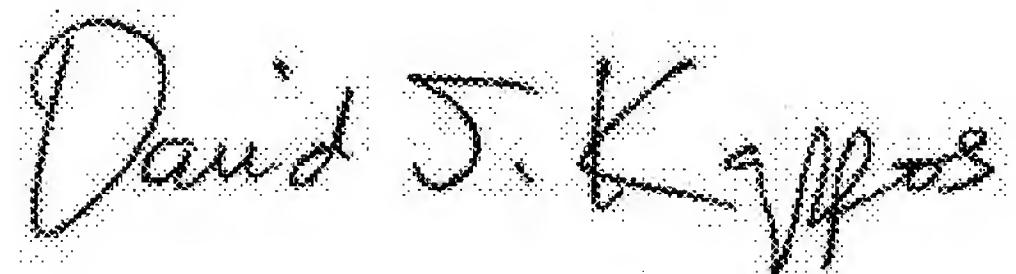
At column 10, lines 10-11, please change “suicide” to --silicide--;

At column 10, lines 19-21, please change “suicide layers 311b and 317b can be formed of a material such as molybdenum suicide (MoSix), tungsten suicide (WSix), tantalum silicide (TaSix), or titanium suicide (TiSix)” to --silicide layers 311b and 317b can be formed of a material such as molybdenum silicide (MoSix), tungsten silicide (WSix), tantalum silicide (TaSix), or titanium silicide (TiSix)--;

At column 19, line 14, please change “suicide” to --silicide--;

At column 19, line 16, please change “suicide” to --silicide--.

Signed and Sealed this  
Twenty-third Day of August, 2011



David J. Kappos  
Director of the United States Patent and Trademark Office